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## FACSIMILE TRANSMISSION COVER SHEET

Date:

November 22, 2005

To:

United States Patent and Trademark Office

Examiner: Ginette Peralta; Art Unit: 2814

Fax:

(571) 273-8300

Re:

Application Serial No.: 09/686,323

Filing Date: 10/9/2000; First Named Inventor: Zhao, Bin

Attorney Docket No.: 02SPE118P-DIV

From:

Farjami & Farjami LLP

Number of pages including the cover sheet: 11

Message:

Dear Ms. Peralta,

Per your request made during our telephonic discussion today (November 22, 2005), enclosed please find the Amendment and Response to Advisory Action of November 2, 2005, which we originally filed on November 10, 2005. As you stated, this filing is a sufficient response to the duplicate Advisory Action of November 15, 2005.

Thank you.

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Attorney Docket No.: 02SPE118P-DIV

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### IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Bin Zhao

Art Unit: 2814

Serial No.: 09/686,323

Examiner: Peralta, Ginette

Filed: October 9, 2000

For: Method of Fabricating an Interconnect

Structure Employing Air Gaps Between Metal Lines and Between Metal Layers

#### AMENDMENT AND RESPONSE TO ADVISORY ACTION

Mail Stop AF
Honorable Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir/Madam:

This is in response to the *Advisory Action* dated November 3, 2005 in the above-referenced patent application. Please enter and consider the following amendments and remarks.